

IN THE CLAIMS

Please amend claim 20 as follows.

1 - 19. (Cancelled)

20. (Currently Amended) A wiring forming method comprising:

a first step of supplying a first liquid containing an insulating material on a substrate to form an insulated pattern on the substrate, the first insulated pattern partially forming a first layer;

a second step of, after the first step, supplying a second liquid containing a conductive material on the substrate to form a first conductive pattern ~~on the same layer that the first insulated pattern has been formed on,~~ the first conductive pattern partially forming the first layer;

a third step of, after the second step, applying the second liquid on the first conductive pattern to form a second conductive pattern on the first conductive pattern, the second conductive pattern partially forming a second layer; and

a fourth step of, after the third step, applying the first liquid on the first layer that the first insulated pattern and the first conductive pattern have ~~been~~ formed ~~[[on]]~~ to form a second insulated pattern ~~on the same~~ as part of the second layer that the second conductive pattern ~~has been partially~~ formed ~~[[on]]~~.

21. (Previously Presented) The wiring forming method according to claim 20, wherein the first insulated pattern and the first conductive pattern are formed so that they come into contact with each other.

22. (Previously Presented) The wiring forming method according to claim 20, wherein the first liquid and the second liquid are supplied by using an ink jet system.